

## **NEW INDUSTRIAL APPLICATIONS FOR ATOMIC LAYER DEPOSITION**

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The atomic layer deposition (ALD) technique has up to now been applied for the manufacturing of electroluminescent displays and silicon integrated circuits. During the past 30 years a broad selection of deposition processes, precursor chemicals and reactors has been developed. This technology base and the remarkable properties of ALD make it one of the key deposition technologies for a range of new industrial applications, including nanofabrication. Some of the new potential industrial applications of ALD are described. The work being done at Micronova for the FinNano technology programme includes new coating solutions for semiconductor lasers, X-ray components, MEMS technology and nanoporous materials.

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